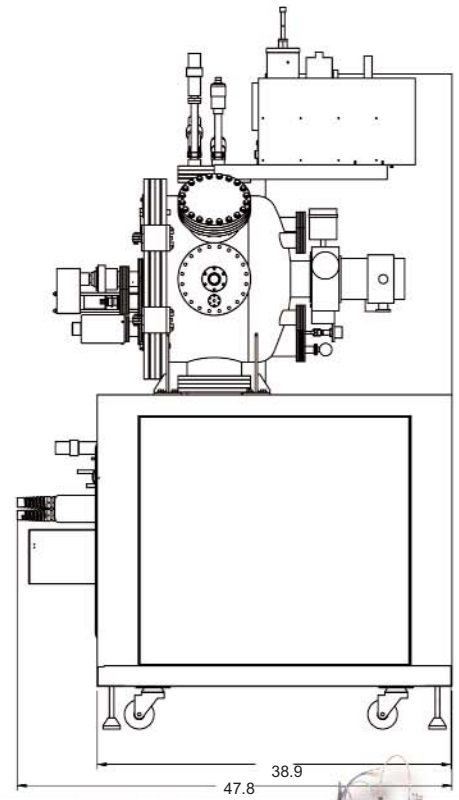
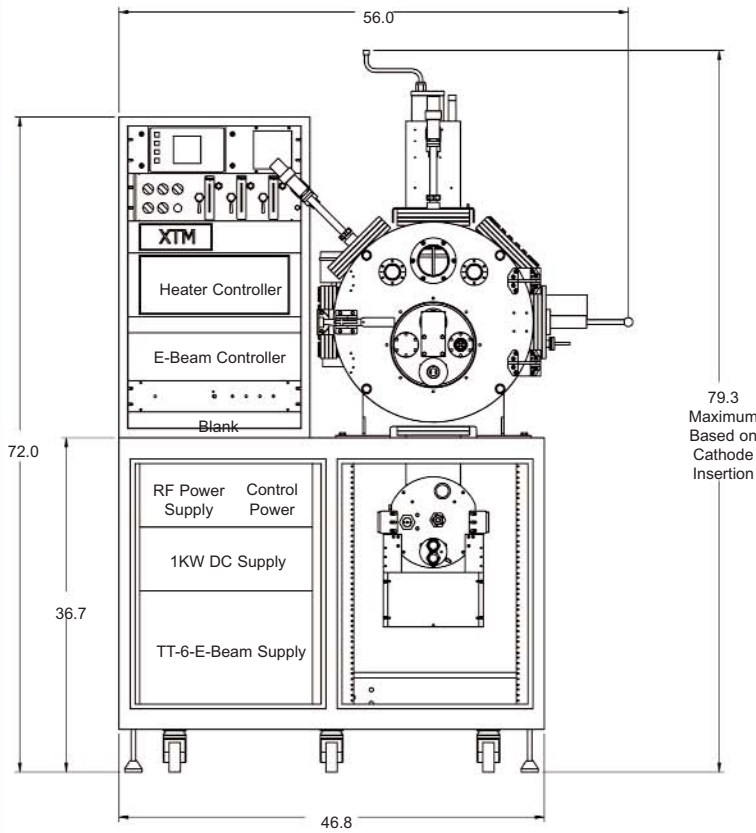


AXXIS is a versatile thin film deposition system for research and development and limited production applications. Both multi-layer and co-deposited films are efficiently handled.

The **AXXIS** system is:

- **Multi-technique**
- **Modular**
- **Cost effective**





Standard Features

- 304 SS Chamber
- Hinged Front Loading Door
- High Vacuum Pumping
- Enclosed Framework
- Small Footprint
- Safety Interlocked Operation

Technical Specifications

Internal Chamber Dimensions:

18" Diameter x 15" deep

Standard Chamber Ports:

Six Radial 8" CF Source Ports

Base Pressure:

5×10^{-7} Torr with Standard Pumping

Pumpdown:

5×10^{-6} In Less Than 15 Minutes

Vacuum Pumping:

250 l/s Turbomolecular Pump (standard)
 500 l/s Turbomolecular Pump (optional)
 1000 l/s MagLev Turbo (optional)
 1500 l/s Cryogenic Pump (optional)
 Oil Free Roughing (optional)

Substrate Holder:

Up to 6" Diameter Substrates
 Substrate Indexing (optional)
 Substrate Rotation (optional)
 Substrate Heating (optional)

Typical Film Uniformity:

< +/-5%

Process Module Options

- Magnetron Sputtering
- E-Beam Evaporation
- Thermal Evaporation
- Computer Control
- High Precision Substrate Tilt
- PECVD
- Plasma Cleaning
- Ion Sources
- High Precision Substrate Rotation

